L Number	Hits	Search Text	DB	Time stamp
-	100	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:26
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adi N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		O2 "O.sub.2") same (hydrofluorocaron CHF	DERWENT;	
		CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3	IBM_TDB	0)0
		F" "CHF.sub.3"))		0000/01/10 16 30
-	22	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/10 16:39
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) same (oxygen	EPO; JPO;	
		02 "0.sub.2") same (hydrofluorocarbon	DERWENT;	·
		hydrofluoromethane \$3fluoromethane methane	IBM_TDB	
		adj \$3fluoride CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3")	******	2003/01/17 13:58
-	8	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 13:58
	•	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	[
		adj N?sub.?) WITH (oxygen O2 "O.sub.2") WITH	EPO; JPO;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	DERWENT;	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM_TDB	
		"CHF.sub.3")) same (Cu copper)	IIGDAE.	2002/01/17 14:00
-	5	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 14:00
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		O2 "O.sub.2") same (hydrofluoroMETHANE	DERWENT;	
		METHYLENE\$3FLUORIDE \$4FLUOROMETHANE methane	IBM_TDB	
		adj \$3fluoride))		0000/01/17 14:00
-	13	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 14:00
1		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) WITH (oxygen 02 "O.sub.2") WITH	EPO; JPO;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	DERWENT;	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM_TDB	
		"CHF.sub.3")) same (Cu copper)) ((etch\$3		
		with (silicon adj nitride Si3N4 "Si.sub.3		
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj		
		N?sub.?)) same (Cu copper) and ((oxygen O2		
		"O.sub.2") same (hydrofluoroMETHANE		
		METHYLENE\$3FLUORIDE \$4FLUOROMETHANE methane		
		adj \$3fluoride)))	HODAM	2002/02/17 11.52
-	67	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:52
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
1		02 "0.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F. sub.2" "CH. sub.3 F" "CHF. sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))	HCDAT.	2003/03/17 11:53
-	55	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:55
1		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB; EPO; JPO;	
		adj N?sub.?)) same (Cu copper) and ((oxygen		
		O2 "O.sub.2") same (hydrofluorocarbon	DERWENT; IBM TDB	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	T T T T DB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
ļ		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
j		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))		

_	22	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:57
}		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "0.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		i i
		"O.sub.2") with (hydrofluorocarbon		
'		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		"CFH. Sub. 3") With (Inert he we at we herrum		
1		neon argon xenon))) and ((oxygen O2	1	
		"O.sub.2") near2 (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon))		2222/22/17 11 56
-	6	((((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:56
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
	i	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
1	1	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		1
		"O.sub.2") near2 (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") near (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near (inert He Ne Ar Xe helium		
1				
	J <u>.</u>	neon argon xenon))		

_	16	((((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:02
-		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
·		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
!		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
İ		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
İ		"O.sub.2") near2 (hydrofluorocarbon		
!		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon))) not ((((etch\$3 with		
		(silicon adj nitride Si3N4 "Si.sub.3		
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj		
		N?sub.?)) same (Cu copper) and ((oxygen O2		
		"O.sub.2") same (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
	ł	neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		İ
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		x
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"0.sub.2") near2 (hydrofluorocarbon		1
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
-	1	neon argon xenon))) and ((oxygen O2		
1		"O.sub.2") near (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		1
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		1
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		1
		"CFH.sub.3") near (inert He Ne Ar Xe helium		1
		neon argon xenon)))		
	l	1	1	

				0000 (00 (17 10 10
-	33	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:13
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB; EPO; JPO;	
		adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM TDB	
İ		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
	1	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		
j [fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
1		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	1	"CFH.sub.3") with (inert He Ne Ar Xe helium	٠	
1		neon argon xenon))) not (((etch\$3 with		
		(silicon adj nitride Si3N4 "Si.sub.3		
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj		
	i	N?sub.?)) same (Cu copper) and ((oxygen O2		1
		"O.sub.2") same (hydrofluorocarbon		, i
	ì	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	1	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
.]		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
ļ		"CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2		
		"O.sub.2") near2 (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	}	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon)))	USPAT;	2003/03/17 12:21
-	0	((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	2003, 03, 11 == 1=
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
	,	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and etch\$3 same (ash\$3		
		(photoresist resist) remov\$3 strip\$4) same		
		((single same one) near chamber)		
_	o	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:21
	1 .	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	DERWENT; IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	15100	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
1	1	"CFH.sub.3") same (inert He Ne Ar Xe helium		
1	1	neon argon xenon))) and ((single same one)		
	1	near chamber)	TIODAM -	2003/03/17 12:21
-	7	((etch\$3 with (silicon adj nitride Si3N4	USPAT; US-PGPUB;	2003/03/1/ 12:21
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	EPO; JPO;	
		adj N?sub.?)) same (Cu copper) and ((oxygen 02 "0.sub.2") same (hydrofluorocarbon	DERWENT;	
1		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((single same one)		
		with chamber)	USPAT;	2004/03/20 13:08
-	1408	etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	2004/05/20 15.00
	1	adj N?sub.?) same (Cu copper)	EPO; JPO;	
		day M. Bub / Bame (ou copper)	DERWENT;	
			IBM_TDB	
L	1			

	· ·	in the delicer odi nitride Si 3N4	USPAT;	2004/03/20 13:11
-	6201	etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)	US-PGPUB; EPO; JPO;	
			DERWENT; IBM TDB	
_	428	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:13
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3	US-PGPUB; EPO; JPO;	
		same ((oxygen 02 "0.sub.2") with	DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
		"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))		
_	115	(etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB;	2004/03/20 13:10
		adi N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
		same ((oxygen 02 "O.sub.2") with	DERWENT; IBM TDB	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"	1511_155	
_		"CHF.sub.3"))	USPAT;	2004/03/20 13:11
-	1234	"Si sub 3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN	EPO; JPO; DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu	IBM_TDB	
		copper)	USPAT;	2004/03/20 13:12
-	114	"Si sub 3 N. sub 4" SiN "SiN. sub x" Si? sub ?	US-PGPUB;	
		adi N?sub.?) and (Cu copper)) and etch\$3	EPO; JPO; DERWENT;	
		same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
		"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
	0.55	Si?sub.? adj N?sub.?) with (Cu copper)	USPAT;	2004/03/20 13:12
_	855	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN	EPO; JPO; DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu	IBM_TDB	
	80	copper) ((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:12
-	80	"Si sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB; EPO; JPO;	
		adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "0.sub.2") with	DERWENT;	
	i	(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
		"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
_	179	Si?sub.? adj N?sub.?) with (Cu copper) (etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:16
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2	US-PGPUB; EPO; JPO;	
		"O sub 2") with (suppress\$3 inhibit\$3	DERWENT;	
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3	IBM_TDB	
_	52	corrosion) (etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:17
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen	US-PGPUB; EPO; JPO;	
		02 "O.sub.2") with (suppress\$3 inhibit\$3	DERWENT;	
	8	prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)	IBM_TDB	
_	38	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:19
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon	US-PGPUB; EPO; JPO;	
		adi nitride Si3N4 "Si.sub.3 N.sub.4" SiN	DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with	IBM_TDB	
		(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
		with (oxidation oxidiz\$3 corrosion)		

-	47	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:19
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) and (Cu copper)) and (silicon	EPO; JPO;	
		adi nitride Si3N4 "Si.sub.3 N.sub.4" SiN	DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu	IBM_TDB	
		copper)) and (oxygen 02 "O.sub.2") with	_	
		(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
		with (oxidation oxidiz\$3 corrosion)		ĺ
	205	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:21
-	203	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
}		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	ļ
		same ((oxygen 02 "0.sub.2") with	DERWENT;	1
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM TDB]
	ļ	"CH.sub.2 F.sub.2" "CH.sub.3 F"	1511_155	1
		"CHF.sub.3"))) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
		copper)) and etch\$3 same ((oxygen 02		
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
	ļ	CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		1
1	1	"CHF.sub.3"))) and (silicon adj nitride		·
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
	1	Si?sub.? adj N?sub.?) with (Cu copper))		
		(((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		1
		adj N?sub.?) same (Cu copper)) and etch\$3		
		same ((oxygen 02 "0.sub.2") with		
		(hydrofluorocaron CHF CH2F2 CH3F CHF3		
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		1
		"CHF.sub.3"))) and (silicon adj nitride		1
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
		Si?sub.? adj N?sub.?) with (Cu copper))		
		Sirsub.? adj N.Sub.?/ with (cu copper//		
		((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) same (Cu copper)) and (oxygen		
		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		İ
1		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
1		copper)) and etch\$3 same ((oxygen O2		
	1	"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		1
		with (suppress\$3 inhibit\$3 prevent\$3		1
		reduce\$3) with (oxidation oxidiz\$3		
	1	corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
1		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
1	1	adj N?sub.?) with (Cu copper)) and (oxygen		
1		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
	1	corrosion)) (((etch\$3 with (silicon adj		
	1	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
	1	HILLIAC SISN4 "SI.SUD.S N.SUD.4" SIN	1	
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
	1	copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
1	1	O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion))		

Γ-	323	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:21
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
:		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
		same ((oxygen 02 "0.sub.2") with	DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		
1		"CHF.sub.3"))) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
İ		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
1	!	copper)) and etch\$3 same ((oxygen O2		1
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		CH3F CHF3 "CH.Sub.2 F.Sub.2 Ch.sub.3 F		
		"CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
		Si?sub.? adj N?sub.?) with (Cu copper))		
		(((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) same (Cu copper)) and etch\$3		Į.
		same ((oxygen 02 "O.sub.2") with		1
		(hydrofluorocaron CHF CH2F2 CH3F CHF3		
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		1
		"CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
	ļ	Si?sub.? adj N?sub.?) with (Cu copper))		
[((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) same (Cu copper)) and (oxygen	1	
		adj Nysub. ?) same (cu copper) / and (oxygen		
		02 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
	1	corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and etch\$3 same ((oxygen O2		
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		
		with (suppress\$3 inhibit\$3 prevent\$3		
		reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		1
		copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
		adj N/Sub.?) with (cu copper) and (oxygen		
		02 "0.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		1
		corrosion)) (((etch\$3 with (silicon adj		İ
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		}
		copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		1
		adj N?sub.?) with (Cu copper)) and (oxygen	1	
1	1	02 "O.sub.2") with (suppress\$3 inhibit\$3		Į.
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion))) ((etch\$3 with (silicon adj		
1		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
		copper)) and (oxygen 02 "O.sub.2") with		
		(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
		with (oxidation oxidiz\$3 corrosion))		
	4	1	USPAT;	2004/03/20 13:21
-	4	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
1		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
		same ((oxygen 02 "O.sub.2") with	DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM TDB	
		(Hydrolluorocaton Chr Chara Char Chra	12122	
		"CH. sub.2 F. sub.2" "CH. sub.3 F"		
		"CHF.sub.3"))) and (oxygen O2 "O.sub.2")		
		with (suppress\$3 inhibit\$3 prevent\$3		
		reduce\$3) with (oxidation oxidiz\$3		
	1	corrosion)	1	1

2004/03/20 13:31 (((etch\$3 with (silicon adj nitride Si3N4 USPAT; "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? US-PGPUB; adj N?sub.?) same (Cu copper)) and etch\$3 EPO; JPO; DERWENT; same ((oxygen 02 "O.sub.2") with IBM TDB (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen 02 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))

-	2	(etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB;	2004/03/20 13:31
		adj N?sub.?) same (Cu copper)) and (etch\$3	EPO; JPO;	
		with (silicon adj nitride Si3N4 "Si.sub.3	DERWENT;	
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj	IBM_TDB	
		N?sub.?) with (Cu copper) with (oxygen 02		
		"O.sub.2") with (hydrofluorocarbon CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))	110000	2004/02/20 12 20
· -	2	(etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT;	2004/03/20 13:32
		adj N?sub.?) and (Cu copper)) and (etch\$3	US-PGPUB; EPO; JPO;	
	1	with (silicon adj nitride Si3N4 "Si.sub.3	DERWENT;	
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj	IBM TDB	
		N?sub.?) with (Cu copper) with (oxygen 02	12.1_122	
		"O.sub.2") with (hydrofluorocarbon CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))		
_	37		USPAT;	2004/03/20 13:41
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) and (Cu copper)) and (etch\$3	EPO; JPO;	
		with (silicon adj nitride Si3N4 "Si.sub.3	DERWENT;	į
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj	IBM_TDB	•
		N?sub.?) same (Cu copper) same (oxygen 02		
		"O.sub.2") same (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))		
_	2	("6033584").PN.	USPAT;	2004/03/20 13:45
_		(0033304 /.FM.	US-PGPUB;	2001/03/20 13:13
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
	7		USPAT	2004/03/20 13:41
-	5		USPAT	2004/03/20 13:43
		"5840629" "5897379").PN.]
-	887		USPAT;	2004/03/20 13:46
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) and (Cu copper)) and (hydrogen	EPO; JPO;	
		H2 "H.sub.2") with (plasma discharge)	DERWENT;	
			IBM_TDB	

"Si. sub. 3 N. sub.4" SiN "SiN N. sub.x" SiYub.? adj N?aub.?) same (Cu copper)) and etch63 same (Coxygen O2 "O. sub.2") with (hydrofluorocaron CHE CHAF2 CHIF CHE3 "CH. sub.2 F. sub.2" "CH. sub.4" SiN "SiN. sub. x" Si?aub.? adj N?aub.?) and (Cu copper) and silven and silven and intride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?aub.? adj N?aub.?) and (Cu copper) and silven and silven and intride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?aub.? adj N?aub.?" cll. corocaron CHE CHAF2 CHIF "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3 "N) and (silicon adj nitride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?aub.? adj N?aub.? with (Cu copper)) (((etch53 with (silicon adj nitride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?aub.? adj N?aub.?" with (hydrofluorocaron CHE CHAF2 CHIF CHE3 "CH. sub.2 F. sub.2" "CH. sub.5 "Si?aub.? adj N?aub.?) same (Cu copper)) and etch63 same ((coxygen O2 "O. sub.2") with (hydrofluorocaron CHE CHAF2 CHIF CHE3 "CH. sub.2 F. sub.2" "CH. sub.5 "Si?aub.? adj N?aub.?) same (Su copper) and (oxygen O2 "O. sub.2") with (suppressSi inhibitS) prevent53 reduce\$3) with (oxidation oxidiz\$3 corrosion) (((etch53 with (silicon adj nitride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.3" SiN. sub.2" Si?aub.? adj n?aub.?) same (Cu copper)) and (oxygen O2 "O. sub.2") with (widrofluorocaron CHE CH2F2 CH3F CHF3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CH. sub.3") and corrosion) (((etch53) with (silicon adj nitride SiJMA "Si. sub.3 N. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.3" SiN. sub.4" SiN "SiN. sub.5" SiN. sub.3" SiN. sub.4" SiN "SiN. sub.5" SiN. sub.4" SiN "SiN. sub.5" SiN. sub.4" SiN. "SiN. sub.5" SiN. sub.4" SiN. "SiN. sub.5" SiN. sub.4" SiN. "SiN. sub.5" SiN. sub.5" SiN. sub.7 adj N?sub.?) with (cxidation oxidiz\$3 corrosion)) ((etch63) with (silicon adj nitride SiJMA "Si. sub.3 N. sub.4"					
adj N?sub.?) same (Cu copper)) with (Chygen Cu Po. Os.ub.2") with (Chygen Cu Po. Os.ub.2") with (Chydrofluorocaron CHF CH2P2 CH3P CH73 "CH.sub.2 F.sub.2 "CH.sub.3 F" "CHF.sub.3")) (((etch53 with (silicon adj nitride SiN4 "Si.sub.3 N.sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper) and etch53 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CH CH2P2 CH3P CH3P CH3P CH3P CH3P CH3P CH3P CH3P		123	((((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:46
adj N?sub.?) same (Cu copper)) with (Chygen Cu Po. Os.ub.2") with (Chygen Cu Po. Os.ub.2") with (Chydrofluorocaron CHF CH2P2 CH3P CH73 "CH.sub.2 F.sub.2 "CH.sub.3 F" "CHF.sub.3")) (((etch53 with (silicon adj nitride SiN4 "Si.sub.3 N.sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper) and etch53 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CH CH2P2 CH3P CH3P CH3P CH3P CH3P CH3P CH3P CH3P			"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
same ((oxygen O2 "0.sub.2") with (hydroflourocaron CRF CH2F2 CH3F CH3F "CH.sub.2 F.sub.2" ((ctch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7aub.7 adj N7sub.7) and (Cu copper)) and etch53 same ((oxygen O2 "0.sub.2") with (hydroflourocaron CHF CH2F2 CH3F CHF3 "CH.sub.3 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.7 adj N7sub.7) with (Cu copper)) (((etch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.7 adj N7sub.7) with (Cu copper)) (((etch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" sizeub.7 "Sin.sub.x" Si7sub.7 adj N7sub.7) same (Cu copper) and etch53 same ((oxygen O2 "O.sub.2") with (hydroflourocaron CH2 CH2F CH37 "CH3 sub.7") same (Cu copper)) ((etch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si2sub.7 adj N7sub.7) with (Cu copper)) ((etch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si2sub.7 adj N7sub.7) same (Cu copper)) and (oxygen O2 "0.sub.2") with (suppress) inhibits3 prevent53 reduce53) with (oxidation oxidiz53 corrosion) (((etch53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.7 adj N7sub.7) same (Cu copper)) and etch53 same ((oxygen O2 "0.sub.2") with (hydrofluorocaron CH5 CH2F2 CH3F CH57 "CH5 "CH53 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.7 adj N7sub.7) same (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.b.4" SiN "SiN.sub.1 "Si7sub.7 adj N7sub.7) same (Cu copper) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.b.4" SiN "SiN.sub.1 "Si7sub.7 adj N7sub.7) same (Cu copper) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.b.4" SiN "SiN.sub.1 "Si7sub.7 adj N7sub.7) and (Cu copper) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.bub.4" SiN "SiN.sub.1 "Si7sub.7 adj N7sub.7) and (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.bub.7" Si7sub.7 adj N7sub.7) with (cu copper)) and (c	ľ			EPO; JPO;	
(hydrofluorocaron CHF CH3F2 CH3F CH3 "CH3 wl.2 F. sub. 2" "CH.F. sub. 3")) (((etch53 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 7 adj N?sub.?) and (Cu copper) and etch5a same (Coxygen O2 "O. sub. 2") with (hydrofluorocaron CHF CH2F2 CH3F CH5F3 "CH. sub. 2 F. sub. 2" "CH. sub. 3") ((etch53 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 7 adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 7 adj N?sub. 7 with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 3 same ((oxygen O2 "O. sub. 2") with (hydrofluorocaron CHF CH3F2 CH3F CH53 same (foxygen O2 "O. sub. 2") with (hydrofluorocaron CHF CH3F2 CH3F CH53 "CH. sub. 3 F" "CHF. sub. 3 F" "CHF. sub. 3 "N. sub. 4" SiN "SiN. sub. x" Si?sub. 3 si?sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 3 si?sub. 3 si?sub. 3 si. sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si. sub. 4" Si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si. sub. 4" Si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si?sub. 3 si. sub. 4" Si?sub. 3 si. sub. 4" Si?sub. 3 si. sub. 3 si. sub. 4" Si?sub. 3 si. sub. 4" Si?sub. 3 si. sub. 4" Si?sub. 3 si. sub. 4" Si?sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 3 si. sub. 4" Si. sub. 3 si. sub. 3 si. sub. 4" Si. sub. 3 si. s			same ((oxygen 02 "O.sub.2") with	DERWENT;	
"CH. sub. 2 F. sub. 2" "H. sub. 3 F" "CHF. sub. 3")) (((etch5) with (silicon adj nitride SiNM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch53 same ((oxygen O2 "O. sub. 2") with (hydrofloucoraron CHF CH2F2 CH3F CH5F CH5 "CH. sub. 2 F. sub. 2" "CH. sub. 3 F" "CHF. sub. 3")) and (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub. 7 adj N?sub.?) with (Cu copper)) (((etch5) with (silicon adj nitride Si3NM "Si. sub. N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch53 same ((oxygen O2 "O. sub. 2") with (hydrofloucoraron CHF CH3F CH3F "CHS sub. 2") sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? "Si. sub. 3" N. sub. 4" SiN "SiN. sub. x" Si?sub.? "Si. sub. 3" N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O. sub. 2") with (suppress) inhibits3 prevent53 reduce53) with (oxidation oxidiz53 corrosion)) (((etch53 with (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch53 same ((oxygen O2 "O. sub. 2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub. 2 F. sub. 2" "CH. sub. 3 F" "CHF. sub. 3")) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibits3 prevent\$3 reduce53) with (oxidation oxidiz\$3 corrosion)) (((etch5) with (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) with (cu copper)) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibits3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion) ((etch6) sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3NM "Si. sub. 3 N. sub. 4" SiN "SiN. sub			(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM TDB	
"CHF.sub.3")) (((etch53 with (silicon adj nitride SiNA "sis.ubu.3" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.4" sub.5				_	
nitride Si3NA "Si.sub.3 N.sub.4" SiN "SiN.sub.x" sirzub.2 adj NYsub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si3rub.? adj NYsub.? with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si2rub.? adj NYsub.?) same (Cu copper)) and etch\$3 same (coxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj NYsub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) same (Cu copper)) and (cxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) same (Cu copper)) and etch\$3 same (Cwxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? Adj Nysub.?) same (Cu copper)) and etch(cth\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? P.sub.2 P.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj Nysub.?) and (Cu copper)) and (citch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj Nysub.?) adj Nysub.?) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.b.X Si?sub.3 N.sub.4" SiN "SiN.b.X Si?sub.? adj Nysub.?) and					
"SiN.sub.x" Si7sub.? add; N7sub.?) and (Cu copper)) and ectof33 same (Coxygen OZ "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.? adj N7sub.?) with (Cu copper)) (((ettof3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) with (Cu copper)) and etch53 same ((oxygen OZ "O. sub.2") with (thydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) same (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) same (Cu copper)) and (oxygen OZ "O.sub.2") with (suppress\$ inhibit\$3 prevent\$3 reduce\$1) with (supress\$ inhibit\$3 prevent\$3 reduce\$2) with (cxidation oxidix\$3 corrosion)) ((etch5a with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.X" Si7sub.? adj N7sub.?) same (Cu copper) and etch\$3 same (loxygen OZ "O. sub.2") with (suppress\$ inhibit\$3 prevent\$3 reduce\$1) with (oxidation oxidix\$3 corrosion)) ((etch5a with (silicon adj nitride Si3N4 "Si.sub.2 F.sub.2" "CH.sub.3")) with (suppress\$ inhibit\$3 prevent\$3 reduce\$1) with (oxidation oxidix\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.2 F.sub.2" same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN sub.X Si7sub.? adj N7sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN sub.X Si7sub.? adj N7sub.?) and (Cu copper)) and (cutch\$3 with (oxidation oxidix\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN sub.X Si7sub.? adj N7sub.?) and (Cu copper)) and (cutch\$3 with (cxidation oxidix\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN sub.X Si7sub.? adj N7sub.?) and (Cu copper)) and (oxygen OZ "O.su					
copper)) and etch\$3 same ((oxygen O2 "0.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH3F "CH.sub.2" F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si3'sub.7 adj N'7sub.7) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?eub.7 adj N'3sub.7) same (Cu copper)) and etch\$3 same (Coxygen O2 "0.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 saj N'3sub.7) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) same (Cu copper)) and (cxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 wisb.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) same (Cu copper)) and etch\$3 same (Oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) same (Cu copper)) and etch(cth\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) same (Cu copper)) and (ctch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'3sub.7) and (Cu copper)) and (ctch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" Si?sub.7 adj N'3sub.7) with (Cu copper)) and (Cu copper)) and (ctch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N'sub.7) and (Cu copper)) and (ctch\$3 with (silicon	ŀ				
"O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. Sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((setch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH5F2 "CHS. sub.2" "CH. sub.3 F" "CHF. sub.3")) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x "Si?sub.? adj N?sub?) same (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (cxidation oxidiz\$3 corrosion)) ((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x "Si?sub.2 adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH5" "CH. sub.2 F sub.2" "CH. sub.3 F" "CHF. sub.3"))) and (oxygen O2 "O. sub.2") with (oxygen O2 "O. sub.2") with (suppress3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x " Sirsub.? adj Nisub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x " Sirsub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" Sin "SiN. sub.x " Sirsub.? adj Nisub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x " Sirsub.? adj N?sub.?) with (cucopper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" Sin	ŀ				
CH3F CHF3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3")) and (silicon adj nitride \$i3N4 "Si.sub.3 N. sub.4" \$iN "\$iN. sub.x" \$i?sub.2 adj NYsub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "si.sub.3 N. sub.4" \$iN "\$iN. sub.x" sizeub.2 Resub.4 "SiN "\$iN. sub.x" \$i?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH53 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CH. sub.3")) and (silicon adj nitride si3N4 "Si.sub.3 N. sub.4" \$iN "\$iN. sub.x" si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride si3N4 "si.sub.3 N. sub.4" \$iN "\$iN. sub.x" si?sub.7 adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride si3N4 "si.sub.3 N. sub.4" \$iN "\$iN. sub.x" si?sub.7 same (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "\$i.sub.3 N. sub.4" \$in "sin.sub.x" \$i?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3"))) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride si3N4 "\$i.sub.3 N. sub.4" \$in "sin.sub.x" \$irsub.? adj Nrsub.?) same (Cu copper)) and (silicon adj nitride si3N4 "si.sub.3 N. sub.4" \$in "sin.sub.x" sipsub.? adj Nrsub.? adj Nrsub.?) adj N?sub.?) with (Cu copper) and (oxygen O2 "O. sub.2") with (Cu copper) and (oxygen O2 "O. sub.2") with (Cu copper) and (oxygen O2 "O. sub.2") with (Cu copper) and (oxygen O2 "O. sub.2") with (Cu copper) and (oxygen O2 "O. sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3 with (silicon adj nitride \$i3N4 "\$i.sub.3 N. sub.4" \$in "sin.sub.x" \$i?sub.? adj Nrsub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "sin.sub.x" \$i?sub.? adj Nrsub.?) and (Cu copper)) and					
"CHF.sub.3")) and (silicon adj nitride Si3MM "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHP CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3MM "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) sin "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidis\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3MM "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 awame ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH3 "CH.sub.2 F.sub.2" CH. Bub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3MM "Si.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 awame (loxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH3" "CH.sub.2 F.sub.2" "CH. Bub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3MM "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3MA "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$5) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (planeama	į				
Si3NM "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.2 add N7sub.?) with (Cu copper)) (((etch\$3 with (silicon add intride Si3N4 "si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CH.sub.2 F.sub.2" "CH.sub.3 F" "CH.sub.2 F.sub.2" "CH.sub.3 F" "CH.sub.2 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) with (Cu copper)) ((etch\$3 with (silicon add intride si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (supress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidis\$3 corrosion)) ((etch\$3 with (silicon add) intride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidis\$3 corrosion)) (((etch\$3 with (silicon add) intride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add intride Si3N4 "si.sub.3 N.sub.4" SiN "siN.sub.x" Si?sub.? add intride Si3N4 "sis.sub.3 N.sub.4" SiN "siN.sub.x" Si?sub.? add intride Si3N4 "sis.sub.3 N.sub.4" SiN "SiN.sub.4" SiN "siN.sub.x" Si?sub.? add intride Si3N4 "sis.ub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidis\$3 corrosion)) (((etch\$3 with (silicon add) intride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? add N?sub.?) and (Cu copper)) and (oxygen O2 "O					·
Sirsub.? adj N?sub.?) with (Cu copper)) (((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch53 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHP CH2F2 CH3F CHF3 "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress53 inhibit53 prevent53 reduce\$3) with (oxidation oxidix53 corrosion)) (((etch53 with (silicon adj nitride Si3N4 "Si.sub.x" Si?sub.?) same (Cu copper)) and etch53 same (loxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 P. sub.2" "CH.sub.3 P" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress53 inhibit53 reduce\$3) with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same (loxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 P. sub.2" "CH.sub.3 P" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress53 inhibit53 prevent53 reduce\$1) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$2) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
(((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.Sub.4" SiN "SiN.sub.2" SiAveb.? adj N7sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CH5.sub.3 N.Sub.4" SiN "SiN.sub.x" Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.Sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) with (silicon adj nitride Si3N4 "Si.sub.3 N.Sub.4" SiN "SiN.sub.x" Si7sub.? adj N7sub.?) with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.Sub.4" SiN "SiN.sub.x" Si?sub.? adj N7sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2P2 CH3F CH3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si	1				
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N7sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with ((hydrofluorocaron CHF CH2F2 CH3F CHF3 "CHF.sub.2")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (citicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (cu copper)) and (oxygen O2 "O.sub.2") with (SiNypress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Cu copper) and (oxygen O2 "O.sub.2") with (Oxydation oxi					
adj NYsub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH sub.2 F sub.2" "CH sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj NYsub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si7sub.? adj NYsub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) and (cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) and (cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj NYsub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibi					
same ((oxygen 02 "0.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CHF.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.7 adj N7sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N7sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (sydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (cu copper) and (cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N7sub.?) and (Cu copper)) and (coyygen O2 "O.sub.					
(hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub. 2 F. usb. 2 " "CH. sub. 3 F" "CHF. sub. 3")) and (silicon adj nitride Si3M4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N7sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. Sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub. 2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub. 2 F. sub. 2" "CH. sub. 3 F" "CHF. sub. 3"))) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub. 2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub. 3 N. sub. 4" SiN "SiN. sub. x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Sin. sub. x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O. sub. 2.") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) (and					
"CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3")) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.7 adj Nrsub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj Nrsub.?) same (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si. sub.3 N. sub.4" \$iN "SiN. sub.x" Si?sub.? adj Nrsub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3")) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride \$i3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (cu copper) and (oxygen O2 "O. sub.2") with (cu copper) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (oxygen O2 "O. sub.2") with (Cu copper)) and (cu copper)) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub.2") with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (cu copper)) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (coxygen O2 "O. sub.2") with (supp					
"CHF, sub.3")) and (silicon adj nitride Si3N4" "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O. sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH. sub.2 F. sub.2" "CH. sub.3 F" "CHF. sub.3"))) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.y) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O. sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2" "H. sub.2") with (plasma					
Si3N4 "Si.sub.3 N.sub.4" SiN "ŠiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si. "SiN.sub.4" SiN "SiN.sub.x" Si?sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "si.sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "si.sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "si.sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si. wb.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2" "H.sub.2") with (plasma					
Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) siN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (cu copper)) and (cu copper) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
((etch53 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" Sil'sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress53 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma	ł				
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O.sub.2") with (cu copper)) and (cygen O2 "O2 "O2 wold.2") with (cypress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (oxidation oxidiz\$3 corrosion))) (detch\$3 with (oxidati			Si?sub.? adj N?sub.?) with (Cu copper))		
adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3M4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "sin.sub.x" Si?sub.? adj N?sub.?) si? sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (SiD.3 N.sub.4" SiN "siN.sub.x" Si?sub.? adj N?sub.?) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "siN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "siN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (coygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "siN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (coygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) (dech\$3 with (oxidation oxidiz\$3 corrosion))) and (chydrogen H2 "H.sub.2") with (plasma					
O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CH58 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidix\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) add (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.2" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (etch\$3 with (silicon adj nitride Si3M4 "Si.sub.3 N.sub.4" SiN "SiN.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) (detch\$3 with (oxidation oxidiz\$3 corrosion))) and (hydrogen HZ "H.sub.2") with (plasma	ì				
prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$iN "\$iN.sub.x" \$i?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same (Coxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? same (Cu copper)) and (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$iN "\$is.sub.3 N.sub.4" \$in "\$is.sub.7 si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$in "\$in.sub.x" \$i?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$iN "sin.sub.x" \$i?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$iN "sin.sub.x" \$i?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$in "\$in.sub.x" \$i?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "\$i.sub.3 N.sub.4" \$in "\$in.sub.x" \$i?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma					
nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$4 SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma	1				
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$\frac{3}{3}\$ same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$\frac{3}{3}\$ inhibit\$\frac{3}{3}\$ prevent\$\frac{3}{3}\$ reduce\$\frac{3}{3}\$ with (oxidation oxidiz\$\frac{3}{3}\$ corrosion)) ((etch\$\frac{3}{3}\$ with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$\frac{3}{3}\$ inhibit\$\frac{3}{3}\$ prevent\$\frac{3}{3}\$ reduce\$\frac{3}{3}\$ with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.4" and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "Si?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (suppress\$\frac{3}{3}\$ inhibit\$\frac{3}{3}\$ prevent\$\frac{3}{3}\$ reduce\$\frac{3}{3}\$ with (oxidation oxidiz\$\frac{3}{3}\$ corrosion)) ((etch\$\frac{3}{3}\$ with (oxidation oxidiz\$\frac{3}{3}\$ corrosion))) ((etch\$\frac{3}{3}\$ with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.7" si?sub.7 adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.4" SiN "SiN.sub.7" Si?sub.7 adj N?sub.7) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$\frac{3}{3}\$ inhibit\$\frac{3}{3}\$ prevent\$\frac{3}{3}\$ reduce\$\frac{3}{3}\$ with (oxidation oxidiz\$\frac{3}{3}\$ corrosion))) ((etch\$\frac{3}{3}\$ with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.7" si?sub.7 adj N?sub.7) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$\frac{3}{3}\$ inhibit\$\frac{3}{3}\$ prevent\$\frac{3}{3}\$ with (oxidation oxidiz\$\frac{3}{3}\$ corrosion))) and (hydrogen H2 "H.sub.2") with (plasma	1]
copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" \$i?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" \$i?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" \$i?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" \$i?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.7 sirsub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride \$i3N4 "Si.sub.3 N.sub.4" \$iN "SiN.sub.x" \$i?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma			nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
"O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((letch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Sis.ub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((letch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (subjeress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) nad (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma					
"O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((letch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Sis.ub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((letch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (subjeress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) nad (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) with (oxygen O2 "O.sub.2") with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma			copper)) and etch\$3 same ((oxygen O2		
CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma			"O.sub.2") with (hydrofluorocaron CHF CH2F2		
"CHF.sub.3")) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma			CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma					
reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (hydrogen H2 "H.sub.2") with (plasma					
corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma			·		
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "Sin.sub.x" Si?sub.? adj N?sub.x" Si?sub.? adj N?sub.?) and (oxygen O2 "O.sub.2") with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$5 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (Suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 reduce\$3) with (oxidation oxidiz\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma	}		prevent\$3 reduce\$3) with (oxidation oxidiz\$3]
nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma			corrosion)) (((etch\$3 with (silicon adi		
"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma		.			
copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma	1				
(suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma					
with (oxidation oxidiz\$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma			copper)) and (oxygen 02 "0.sub.2") with		
(hydrogen H2 "H.sub.2") with (plasma		ļ			
		Ì			
discharge)					
			discharge)	L	<u> </u>

75 (((etch\$3 with (silicon adj nitride Si3N "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?su	4 USPAT; b.? US-PGPUB;	2004/03/20 13:47
ugi sub 2 M sub 4 H CiN HCiN cub x H Ci2cui	b.? US-PGPUB:	
"S1.Sub.3 N.Sub.4" SIN "SIN.Sub.A SI:Su		
adj N?sub.?) same (Cu copper)) and etch\$	3 EPO; JPO;	
same ((oxygen 02 "0.sub.2") with	DERWENT;	
(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
"CH.sub.2 F.sub.2" "CH.sub.3 F"	_	
"CHF.sub.3"))) (((etch\$3 with (silicon a	di	
nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
"SiN.sub.x" Si?sub.? adj N?sub.?) and (C	'u	}
copper)) and etch\$3 same ((oxygen O2		
"O.sub.2") with (hydrofluorocaron CHF CH	2F2	
CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F	.,	
"CHF.sub.3"))) and (silicon adj nitride		
Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
Si?sub.? adj N?sub.?) with (Cu copper))		
(((etch\$3 with (silicon adj nitride Si3N	4	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?su	b.?	
adj N?sub.?) same (Cu copper)) and etch\$		-
same ((oxygen O2 "O.sub.2") with	-	
(hydrofluorocaron CHF CH2F2 CH3F CHF3		
"CH.sub.2 F.sub.2" "CH.sub.3 F"		
"CHF.sub.3"))) and (silicon adj nitride		
Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
Si?sub.? adj N?sub.?) with (Cu copper))		
((etch\$3 with (silicon adj nitride Si3N4		
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?su	h 2	
adj N?sub.?) same (Cu copper)) and (oxyg	en l	
O2 "O.sub.2") with (suppress\$3 inhibit\$3		
prevent\$3 reduce\$3) with (oxidation oxid	liz\$3	
corrosion)) (((etch\$3 with (silicon adj	12,5	1
nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu	
copper)) and etch\$3 same ((oxygen O2	eu	
"O.sub.2") with (hydrofluorocaron CHF CH	12 F2	
CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F		
"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		
with (suppress\$3 inhibit\$3 prevent\$3		
reduce\$3) with (oxidation oxidiz\$3		
corrosion)) (((etch\$3 with (silicon adj		
nitride Si3N4 "Si.sub.3 N.sub.4" SiN	Cu	
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu	
copper)) and (silicon adj nitride Si3N4	h 2	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?su		
adj N?sub.?) with (Cu copper)) and (oxyg		1
O2 "O.sub.2") with (suppress\$3 inhibit\$3		
prevent\$3 reduce\$3) with (oxidation oxid	11253	
corrosion)) (((etch\$3 with (silicon adj		
nitride Si3N4 "Si.sub.3 N.sub.4" SiN	•••	
"SiN.sub.x" Si?sub.? adj N?sub.?) and (C	.u	
copper)) and (silicon adj nitride Si3N4	.h 2	1
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?su		
adj N?sub.?) with (Cu copper)) and (oxyg	Jen	
O2 "O.sub.2") with (suppress\$3 inhibit\$3	311-40	1
prevent\$3 reduce\$3) with (oxidation oxid	112\$3	
corrosion))) and (hydrogen H2 "H.sub.2"	')	
with (plasma discharge)		

(((etch\$3 with (silicon adj nitride Si3N4 2004/03/20 13:48 USPAT; US-PGPUB; "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen EPO; JPO; DERWENT; O2 "O.sub.2") with (suppress\$3 inhibit\$3 IBM TDB prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen 02 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu 3/copper)1 and 1(silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN SiN.sub.x" Si?sub.?

Search History

C:\APPS\EAST\Workspaces\\Destricts\\JPS\\JPS\C656-dffer)) and (oxygen

O2 "O.sub.2") with (suppress\$3 inhibit\$3

USPAT; 2004/03/20 13:48 (((etch\$3 with (silicon adj nitride Si3N4 US-PGPUB; "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen EPO; JPO; DERWENT; O2 "O.sub.2") with (suppress\$3 inhibit\$3 IBM TDB prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4

prevent\$3 reduce\$3) with (oxidation oxidiz\$3